CLAIMS

1. A plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein the protective layer includes carbon and silicon.

2. A plasma display panel as claimed in claim 1, wherein a protective layer is made of magnesium oxide including silicon with 5×10^{18} atoms/cm^3 to 2×10^{21} atoms/cm^3, and carbon with 1×10^{18} atoms/cm^3 to 2×10^{21} atoms/cm^3.

3. A plasma display panel as claimed in claim 2, wherein the number of carbon atoms is greater than that of silicon.

4. A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein a process for forming the protective layer is a process for forming a film using a material for a protective layer, including carbon and silicon.

5. A method of manufacturing a plasma display panel as claimed in claim 4, wherein a material for a protective layer is magnesium oxide including carbon and silicon; wherein the density of carbon ranges from 5 ppm to 1,500 ppm by weight; and wherein the density of silicon ranges from 7 ppm to 8,000 ppm by weight.

6. A method of manufacturing a plasma display panel as claimed in claim 4, wherein a material for a protective layer is magnesium oxide including silicon carbide; and wherein the density of silicon carbide ranges from 40 ppm to 12,000 ppm by weight.

7. A method of manufacturing a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein carbon and silicon are added in the protective layer after the protective layer is formed on the dielectric layer.

8. A material for a protective layer of a plasma display panel in which a dielectric layer is formed so that the dielectric layer covers a scanning electrode and a sustain electrode formed on a substrate, and in which a protective layer is formed on the dielectric layer, wherein the material for a protective layer includes carbon and silicon.

9. A material for a protective layer of a plasma display panel as claimed in claim 8, wherein a material for a protective layer is made of magnesium oxide including carbon and silicon; wherein the density of the carbon ranges from 5 ppm to 1,500 ppm by weight; and wherein the density of the silicon ranges from 7 ppm to 8,000 ppm by weight.

10. A material for a protective layer of a plasma display panel as claimed in claim 8, wherein a material for a protective layer is made of magnesium oxide including silicon carbide; and wherein the density of the silicon carbide ranges from 40 ppm to 12,000 ppm by weight.